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Commissioner for Patents, Alexandria, VA 22313-1450.

5/25/04  
(Date of Deposit)

Karen Cinq-Mars  
(Signature)

5/25/04  
(Date)

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In Re Application of : May 18, 2004  
Brodsky et al. :  
Serial No. 10/709,406 : Examiner:  
Filed: 05-03-04 : IBM Corporation  
Dept. 18G/Bldg. 300-482  
Title: METHOD TO REDUCE PHOTORESIST 2070 Route 52  
PATTERN COLLAPSE BY CONTROLLED Hopewell Junction  
SURFACE MICROROUGHENING : New York 12533-6531

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents  
P. O. Box 1450  
Alexandria, VA 22313-1450

Sir:

In compliance with the duty of disclosure under  
37 C.F.R. § 1.56 and in accordance with the practice under  
37 C.F.R. §§ 1.97 and 1.98, the Examiner's attention is directed to  
the document listed on the enclosed Form PTO-1449. A copy of the  
listed document is also enclosed.

It is respectfully requested that the above information be  
considered by the Examiner and that a copy of the enclosed Form  
PTO-1449 be returned indicating that such information has been  
considered.

Applicants undersigned attorney may be reached by telephone

FIS920030360US1

at (845) 894-6919. All correspondence should continue to be directed to the below listed address.

Respectfully submitted,

A handwritten signature in dark ink, appearing to read "Todd M. C. Li". The signature is fluid and cursive, with a horizontal line drawn underneath it.

Todd M. C. Li  
Attorney for Applicants  
Registration No.45,554

INTERNATIONAL BUSINESS MACHINES CORPORATION  
Intellectual Property Law Department  
B/300-482  
2070 Route 52  
Hopewell Junction, New York 12533  
Facsimile: (845) 892-6363

TML/kcm

FORM PTO-1449 (Modified)		ATTY. DOCKET NO. <b>FIS920030360US1</b>	SERIAL NO. <b>10/709,406</b>
LIST OF PATENTS AND PUBLICATIONS FOR APPLICANT'S INFORMATION DISCLOSURE STATEMENT		APPLICANT: <b>BRODSKY ET AL.</b>	
(Use several sheets if necessary)		FILING DATE:	GROUP:

REFERENCE DESIGNATION **U.S. PATENT DOCUMENTS**

EXAMINER INITIALS	DOCUMENT NUMBER	ISSUED DATE	NAME	CLASS	SUBCLASS	FILING DATE (IF APPRO.)

**FOREIGN PATENT DOCUMENTS**

DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION
					YES NO

**OTHER ART (Including Author, Title, Date, Pertinent Pages, etc.)**

CA	S. Lee et al. "New Approach for Pattern Collapse Problem by Increasing Contact Area at Sub-100nm Patterning," Proc. SPIE – The International Society for Optical Engineering, June 2003, pp. 166-174 (Vol. 5039).

EXAMINER

DATE CONSIDERED

**EXAMINER:** Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.